

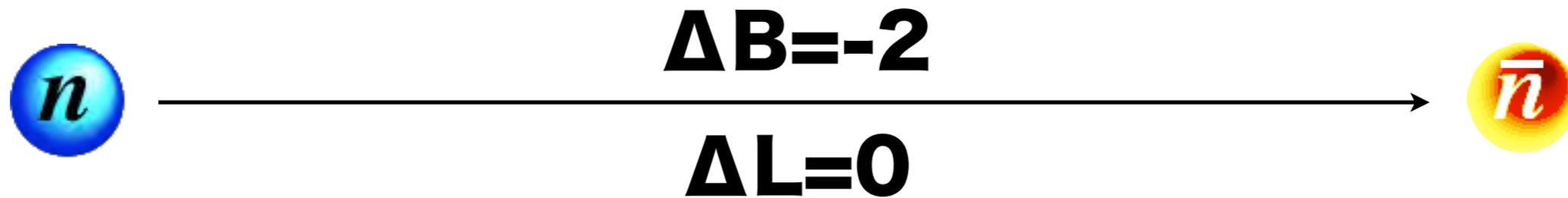
Neutron Mirror Optics and participation of Japan

H.M.Shimizu

Dept. Phys., Nagoya University

hirohiko.shimizu@nagoya-u.jp

$n\bar{n}$ oscillation



free neutron

$$\tau_{n\bar{n},\text{free}} > 8.6 \times 10^7 \text{ s (CL = 90\%)}$$

$$L = \bar{\psi} M \psi$$

$$\psi = \begin{pmatrix} n \\ \bar{n} \end{pmatrix} \quad M = \begin{pmatrix} E_0 & c^2 \delta m \\ c^2 \delta m & E_0 \end{pmatrix}$$

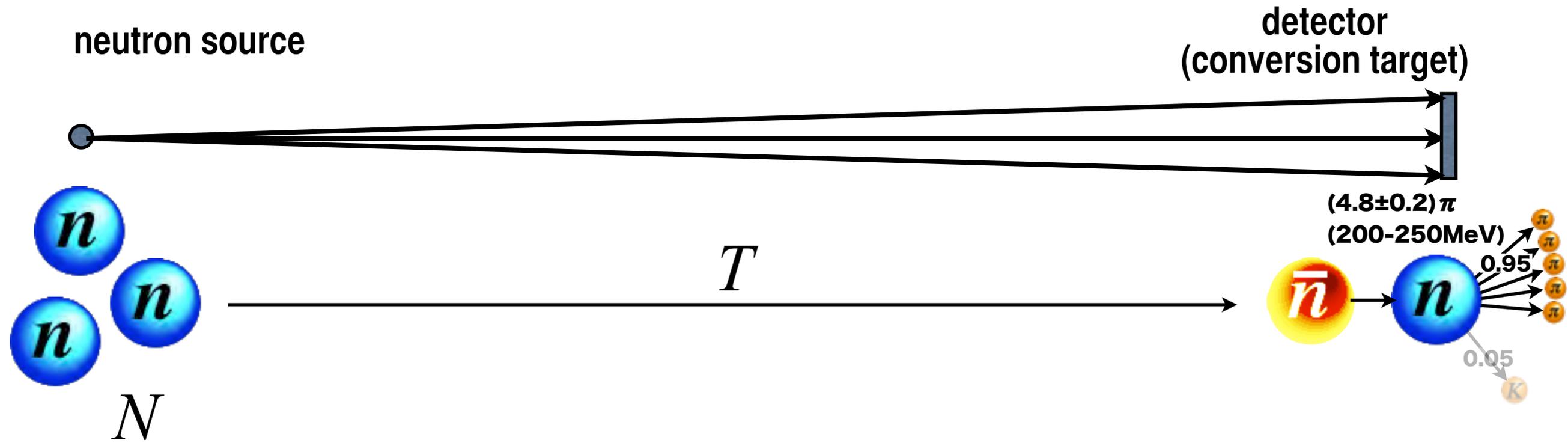
$$|n_{1,2}\rangle = \frac{1}{\sqrt{2}} (|n\rangle \pm |\bar{n}\rangle)$$

$$m_{1,2} = m_n \pm \delta m$$

$$I(t) = I(0) \sin^2 \frac{c^2 \delta m}{\hbar} t$$

$n\bar{n}$ oscillation measurement

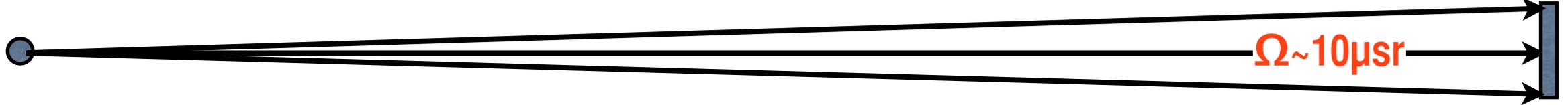
$$\text{FOM} \equiv \langle NT^2 \rangle$$



simple flight path

$$\text{FOM} \equiv \langle NT^2 \rangle$$

neutron source

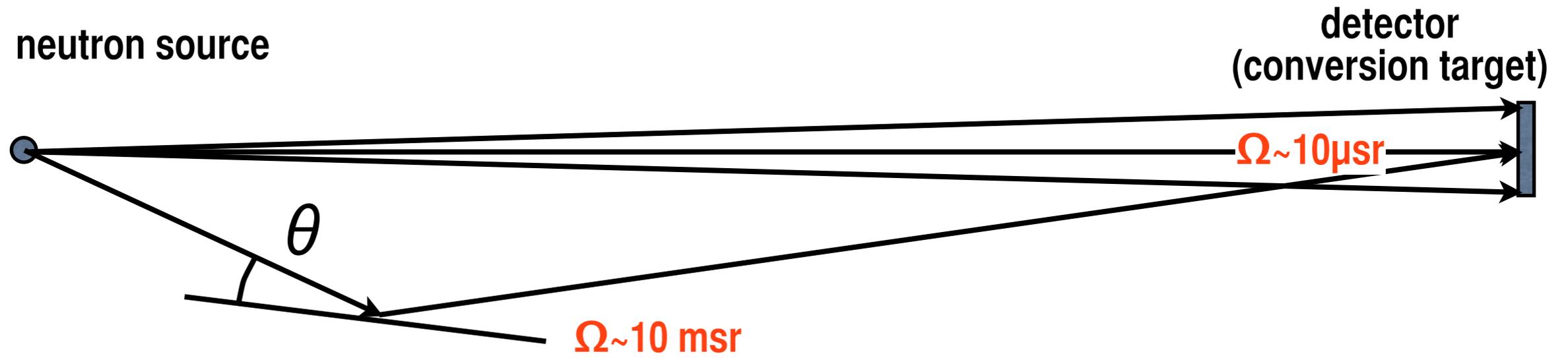


detector
(conversion target)

$\Omega \sim 10 \mu\text{sr}$

additional acceptance with focusing optics

$$\text{FOM} \equiv \langle NT^2 \rangle$$



Neutron Reflection



Fermi potential

$$U = \frac{2\pi\hbar^2}{m_n} bN$$

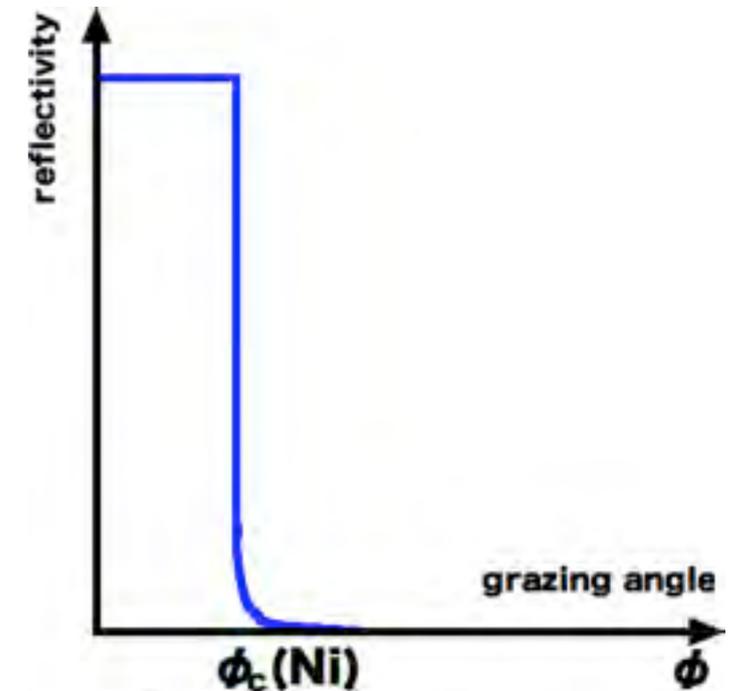
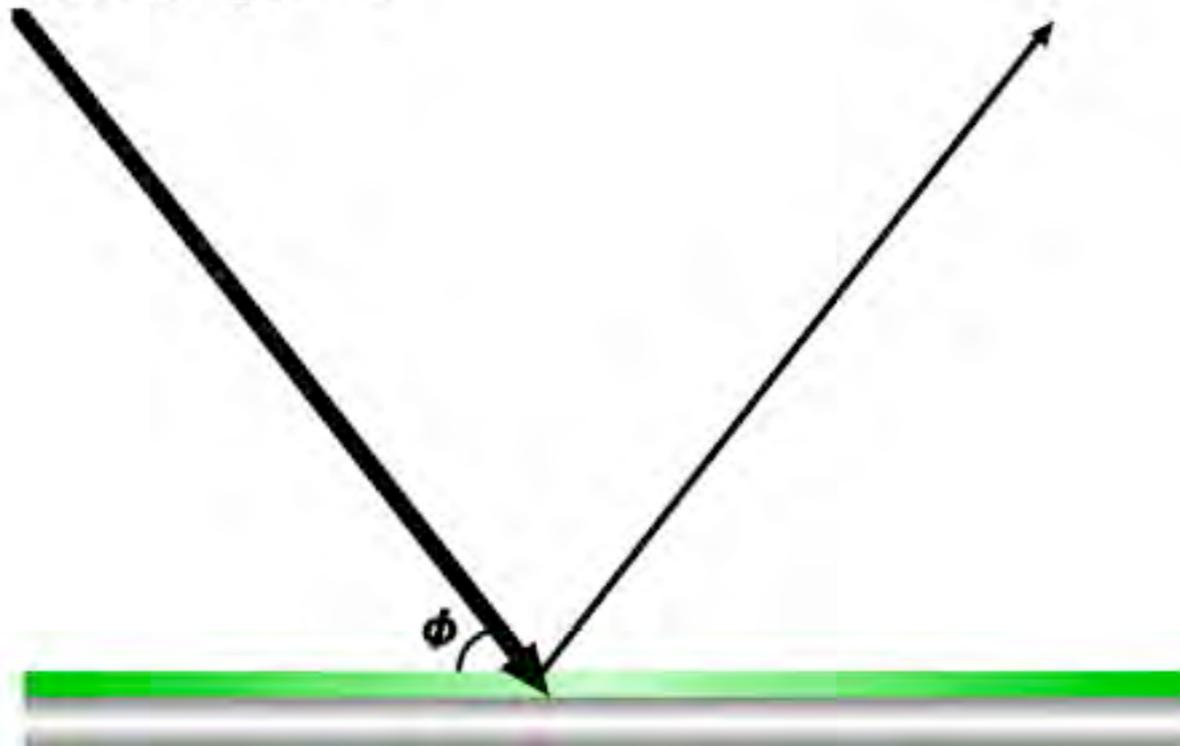
m_n : neutron mass
 b : scattering length
 N : atom number density

neutron wavelength : λ

+243neV



Fermi potential 0



$v_{\perp} = 7 \text{ m/s}$

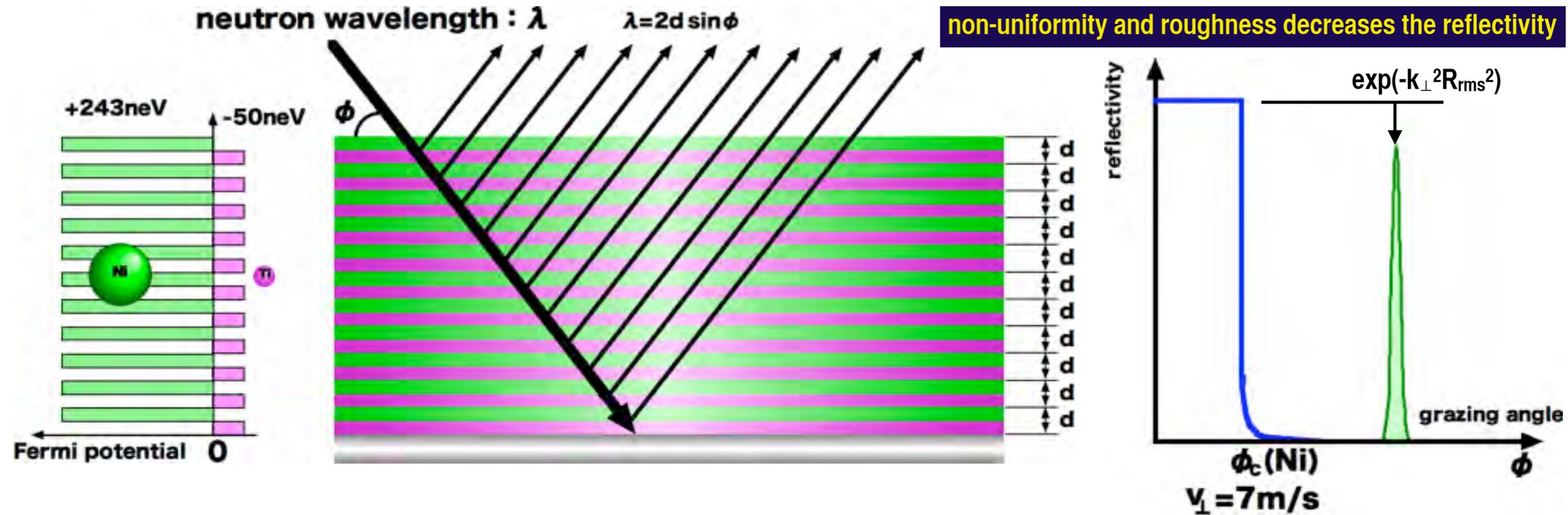
critical angle of total reflection

$$\phi_c(\text{Ni}) / \lambda = 1.7 \text{ mrad/\AA}$$

$$v_{\perp}(\text{Ni}) = 7 \text{ m/s}$$



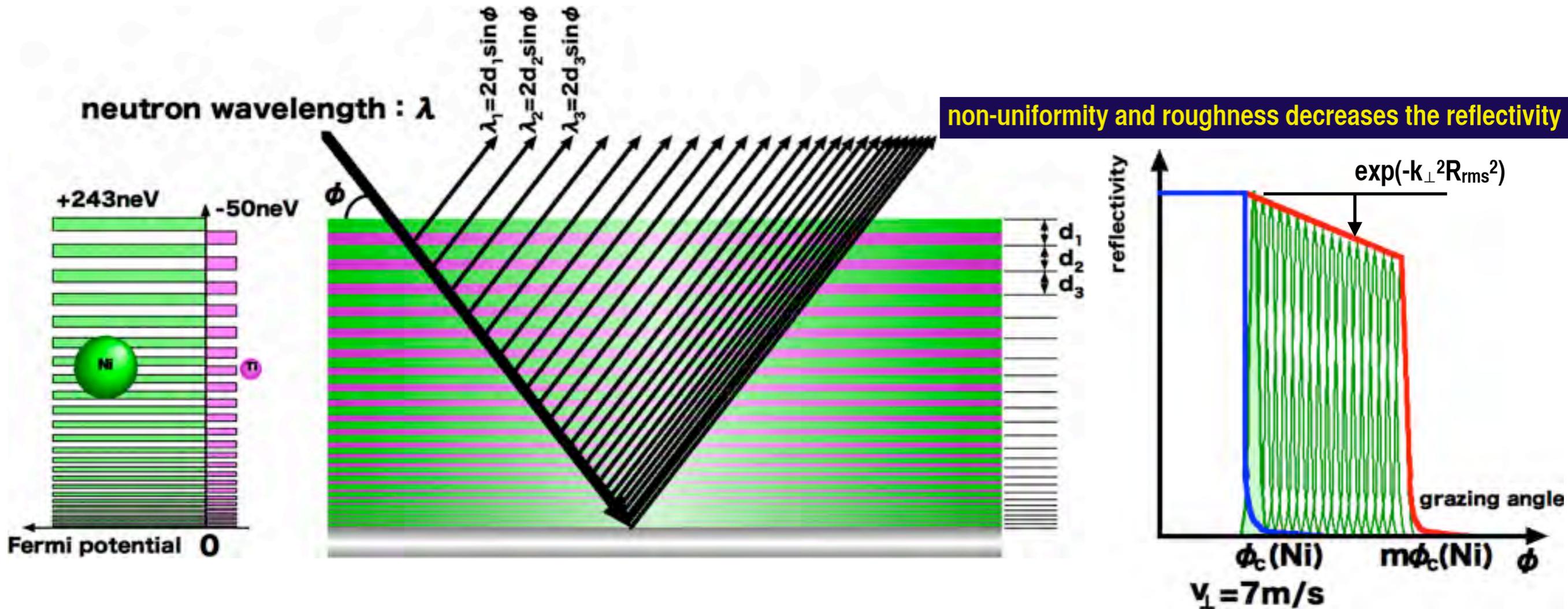
Multilayer Mirror (Monochromatic)



$\phi_c(\text{Ni}) / \lambda = 1.7 \text{ mrad/\AA}$
 $v_{\perp}(\text{Ni}) = 7 \text{ m/s}$



Supermirror



$$m = \phi_c / \phi_c(\text{Ni}) = v_c(\text{Ni}) / v_c$$

$$\phi_c(\text{Ni}) / \lambda = 1.7 \text{ mrad/\AA}$$

$$v_{\perp}(\text{Ni}) = 7 \text{ m/s}$$

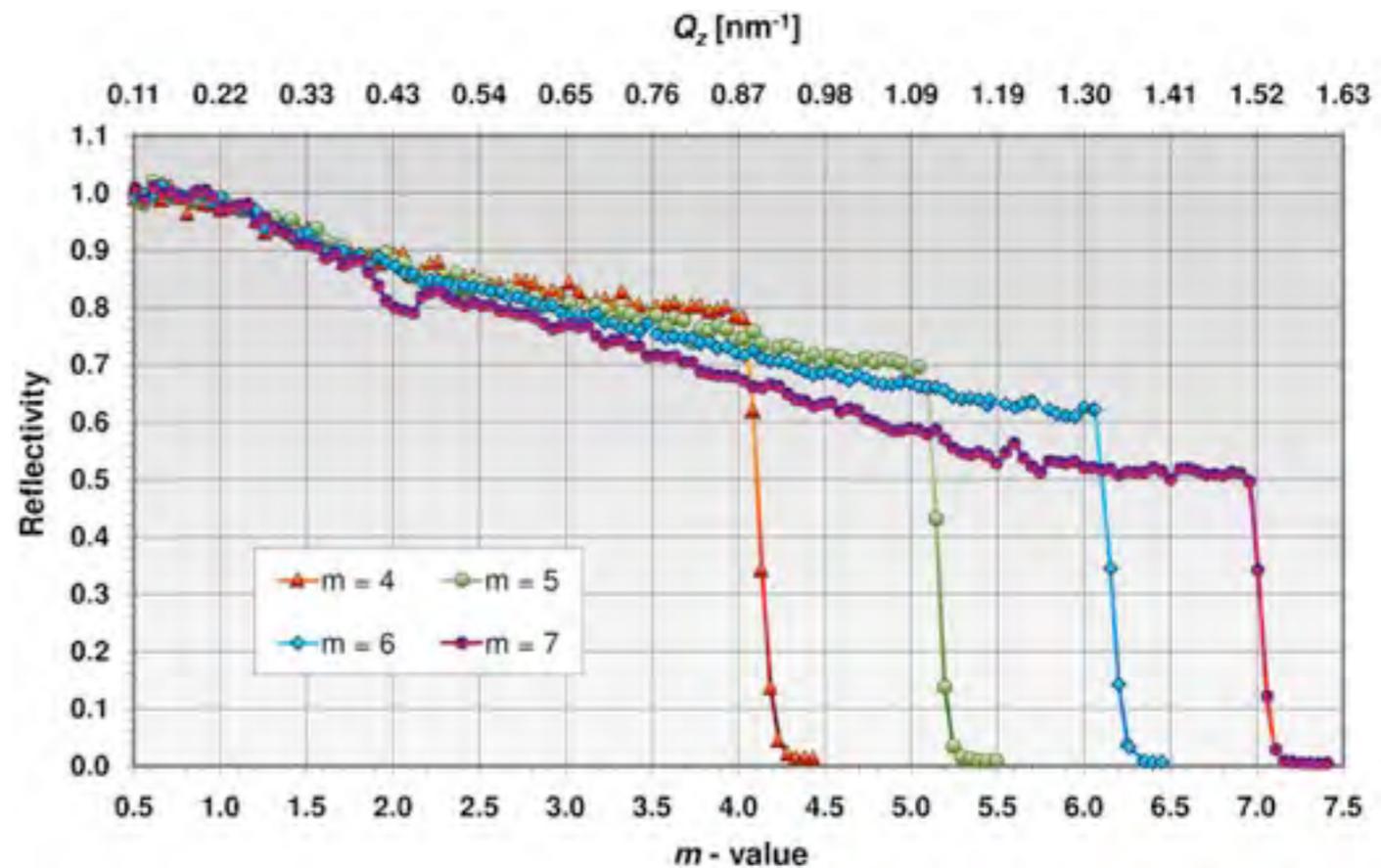


supermirrors $m \leq 7$

$m=4-7$ Supermirrors

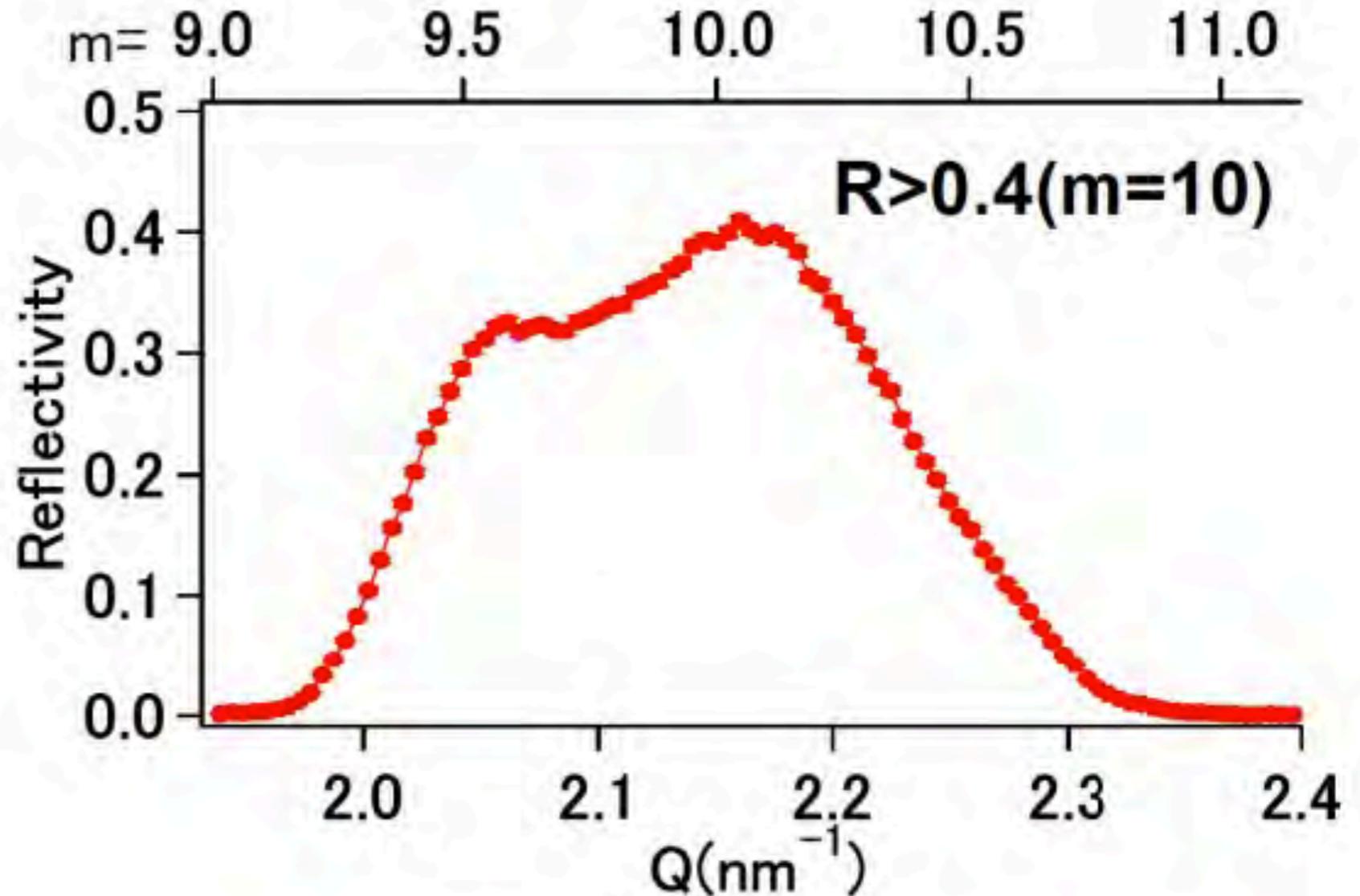
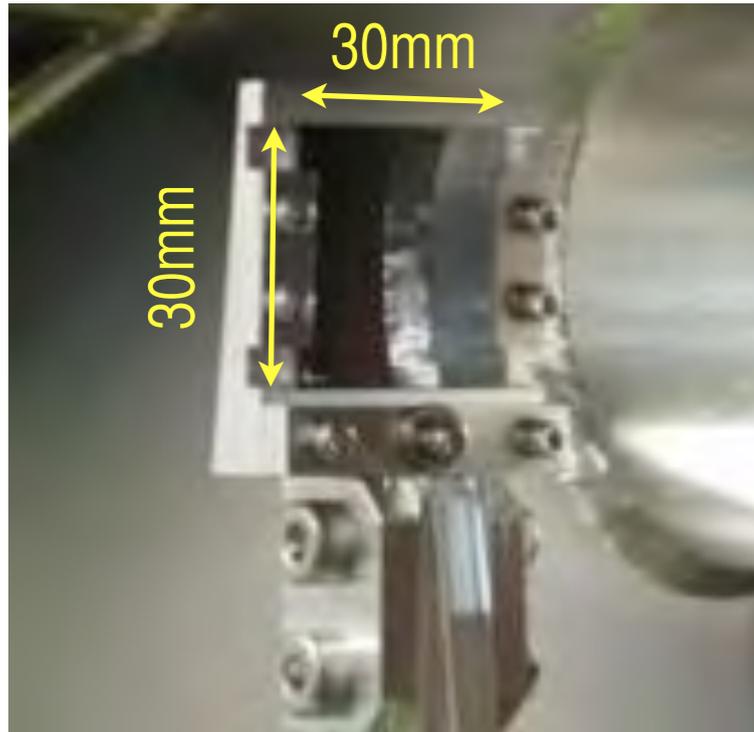
<http://www.swissneutronics.ch/>

Supermirror: commercially available up to $m=7$ ($v_{\perp}=50\text{m/s}$)



wide-band multilayer (quasi-monochromatic) reflectors $m \leq 10$

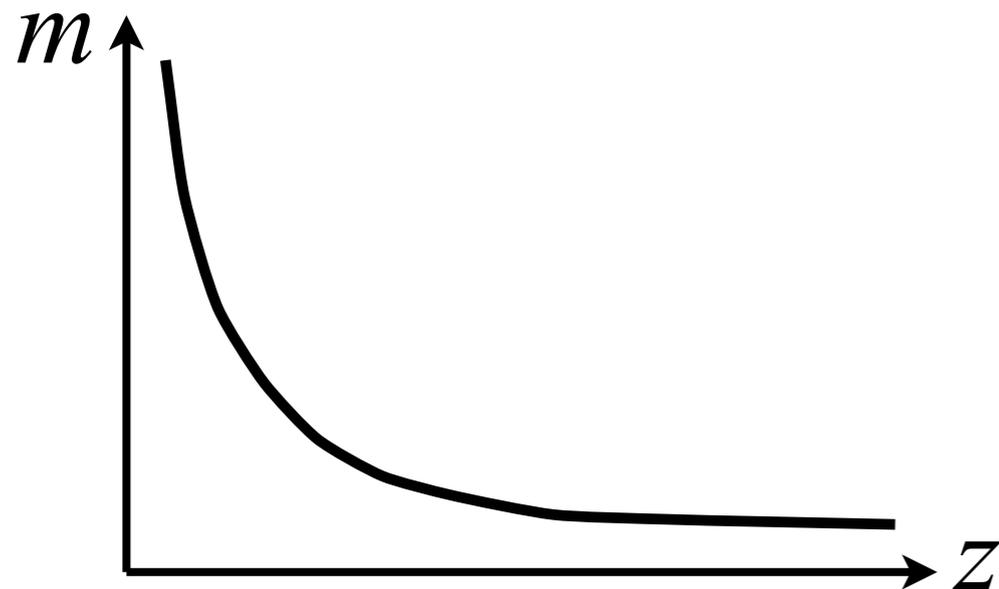
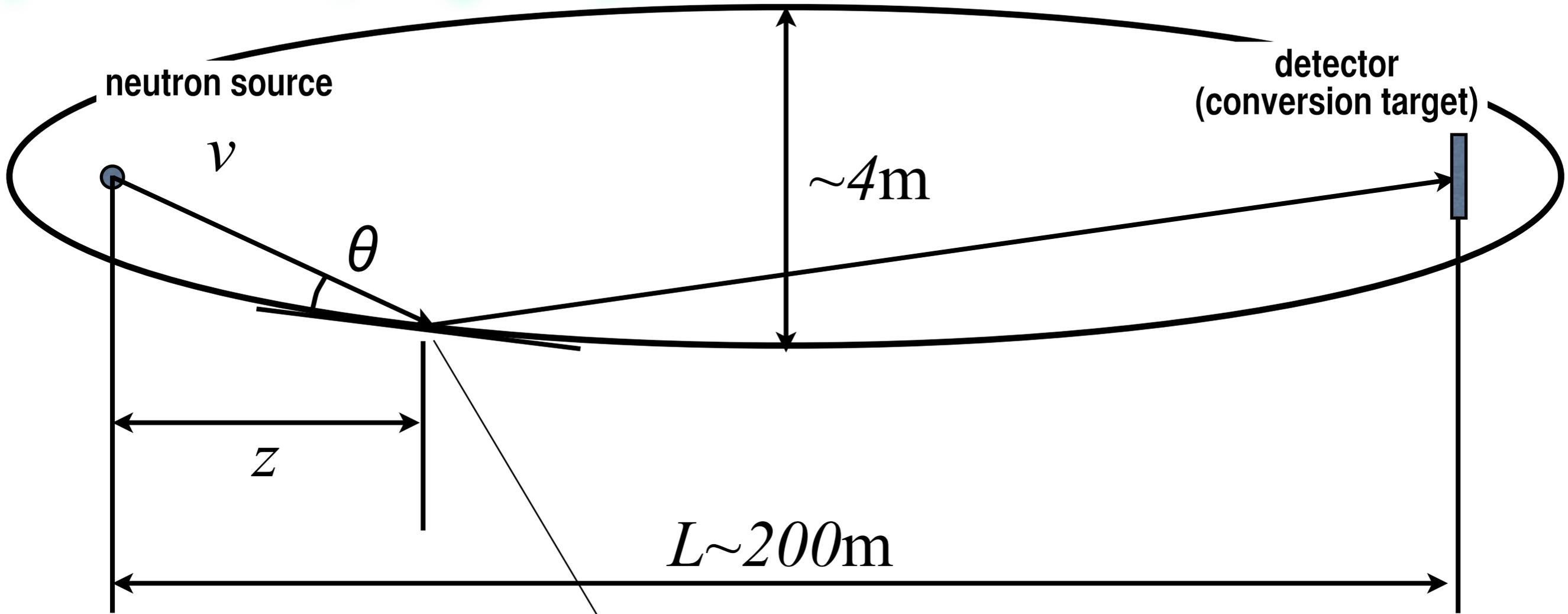
$m=10$ NiC/Ti wide-band quadruple-stack multilayer



85060 bilayers in total = $4 \times (10336 + 10929)$ bilayers
quadruple-stack of double-sided multilayer mirrors

point source, no gravity, monochromatic

FOM $\equiv \langle NT^2 \rangle$

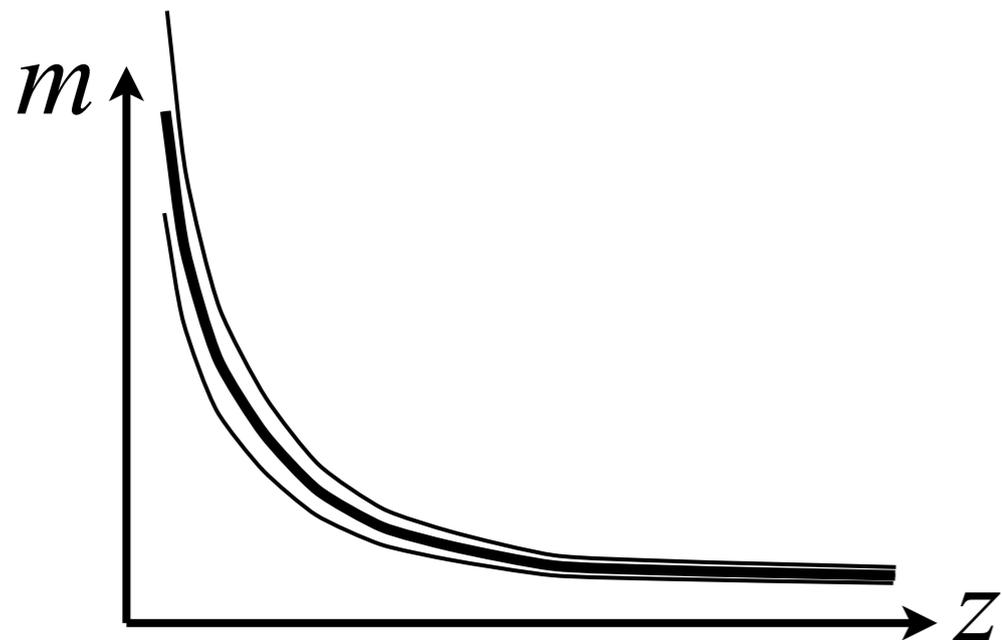
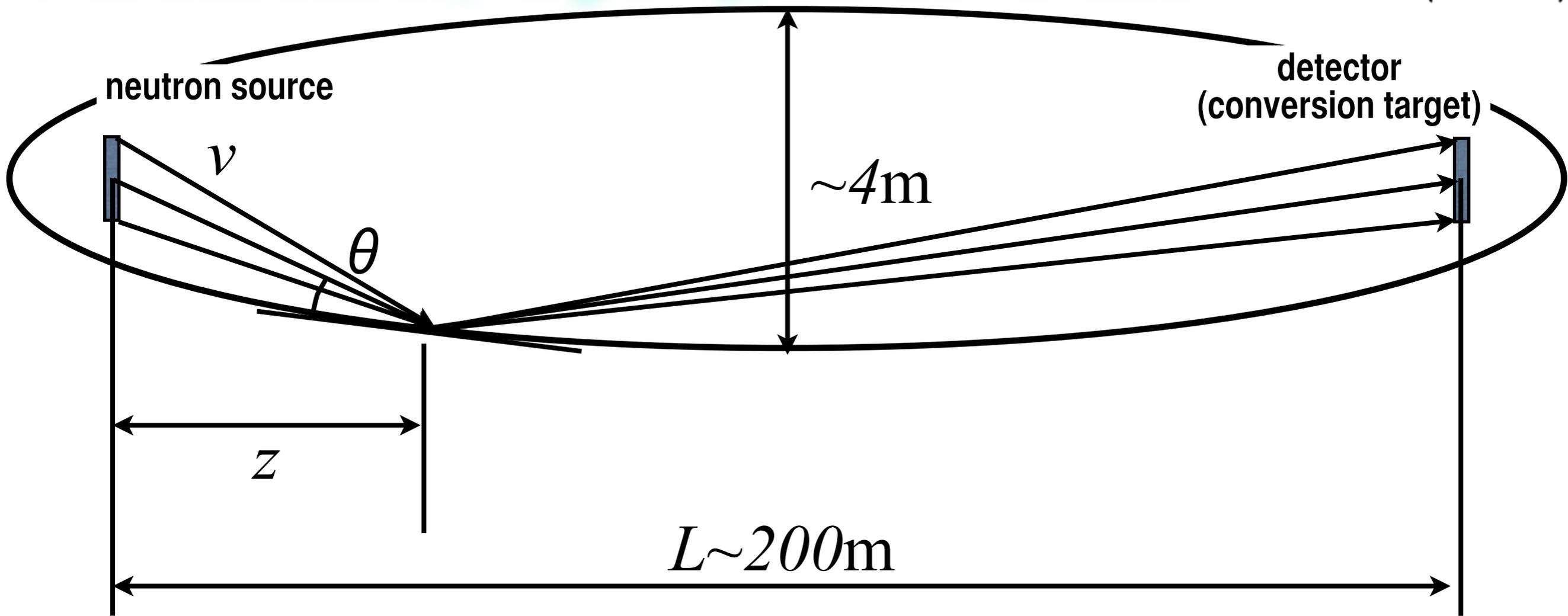


$$m(z) = \frac{v \sin \theta(z)}{7[\text{m/s}]}$$

critical velocity of
total reflection of
natural Ni

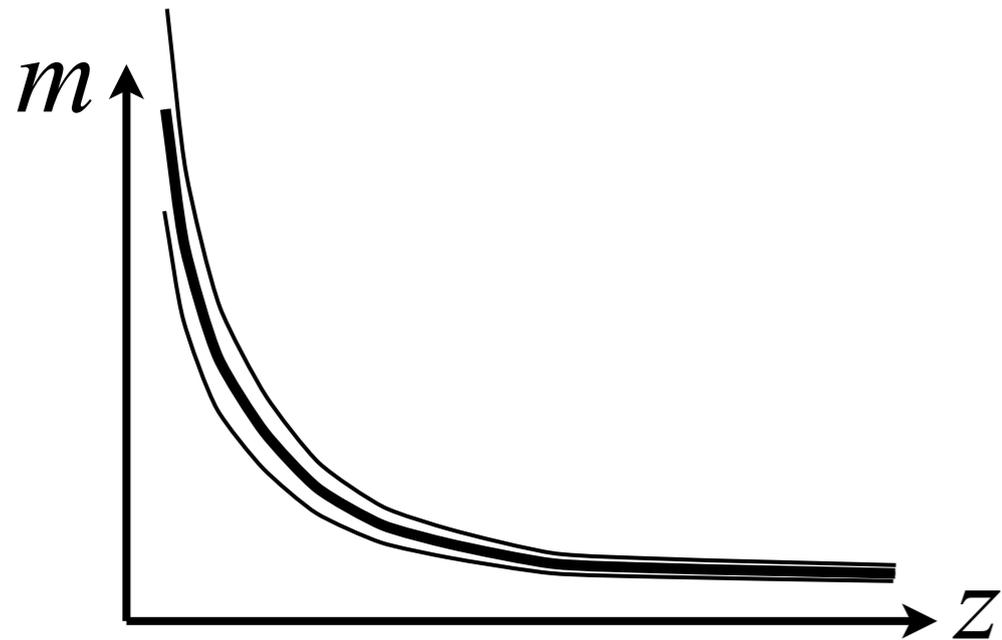
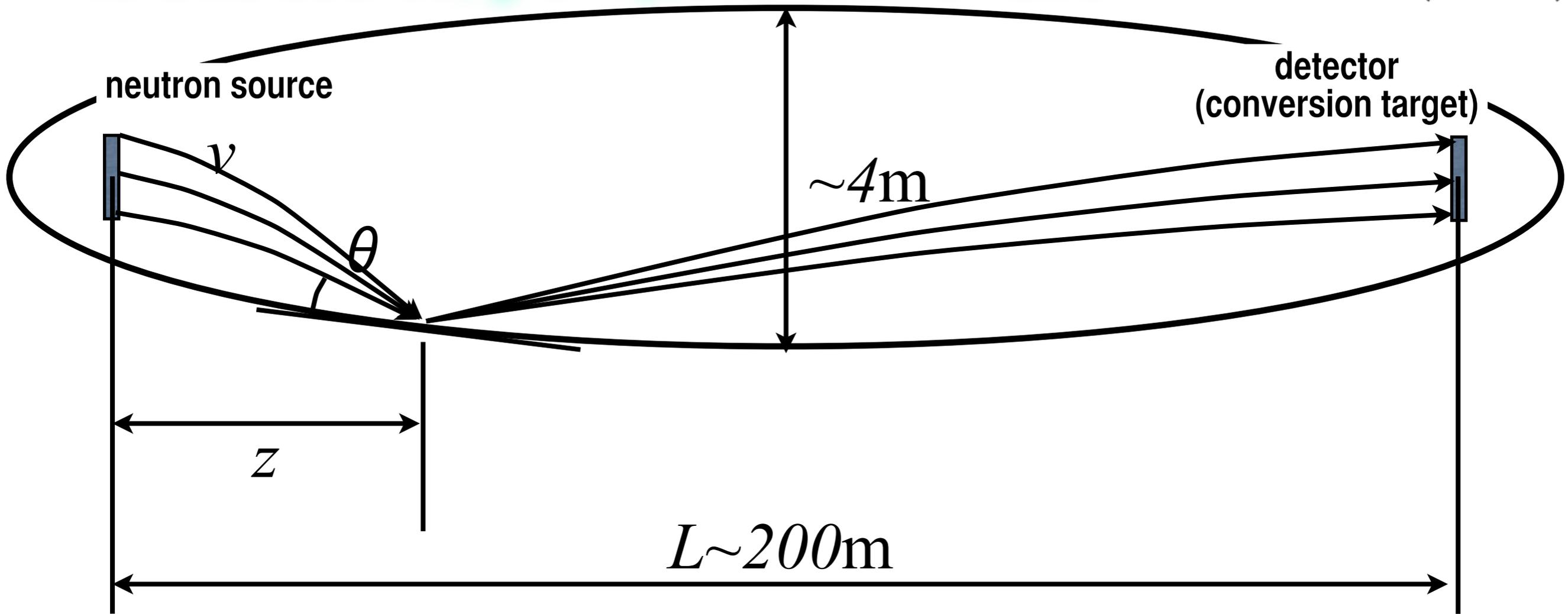
We need multilayer mirror to go beyond $m \sim 1$.

finite-size source, no gravity, monochromatic FOM $\equiv \langle NT^2 \rangle$



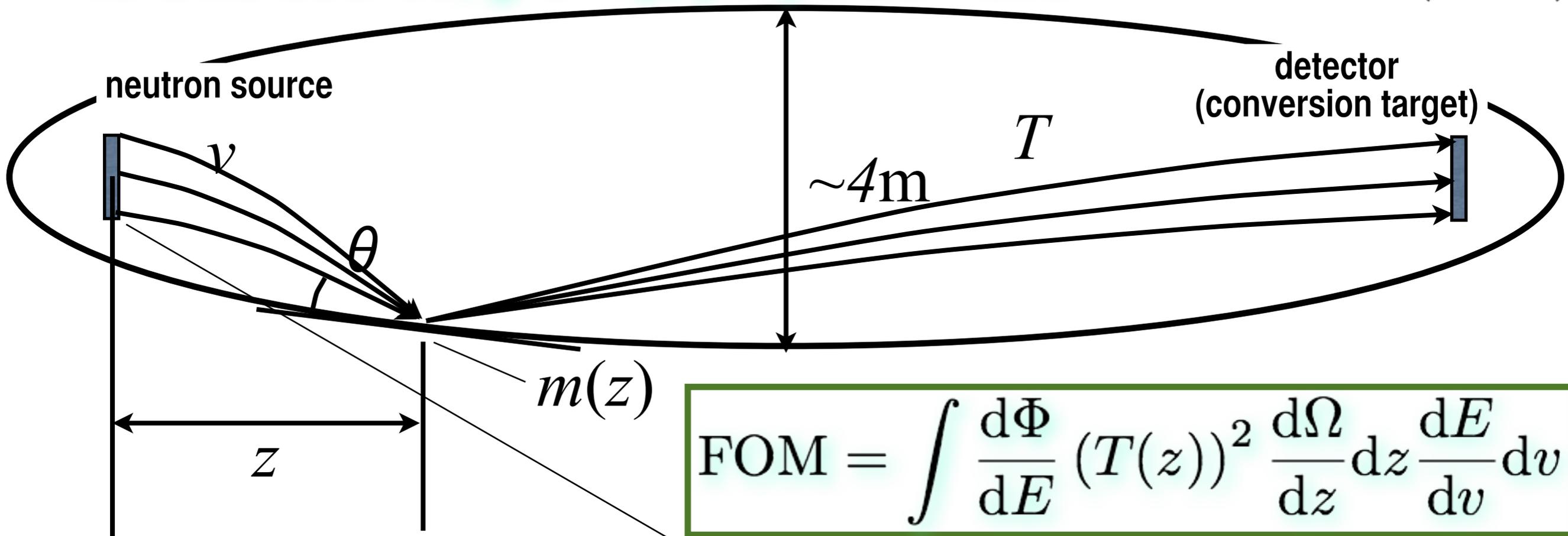
finite-size source, gravity, monochromatic

$$\text{FOM} \equiv \langle NT^2 \rangle$$

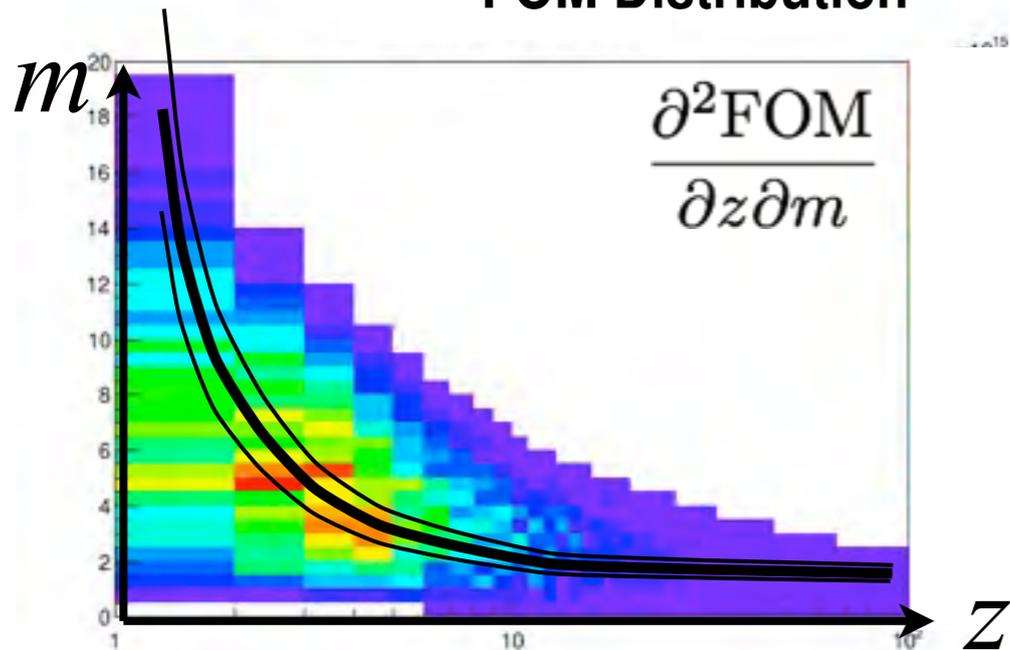


finite-size source, gravity, polychromatic

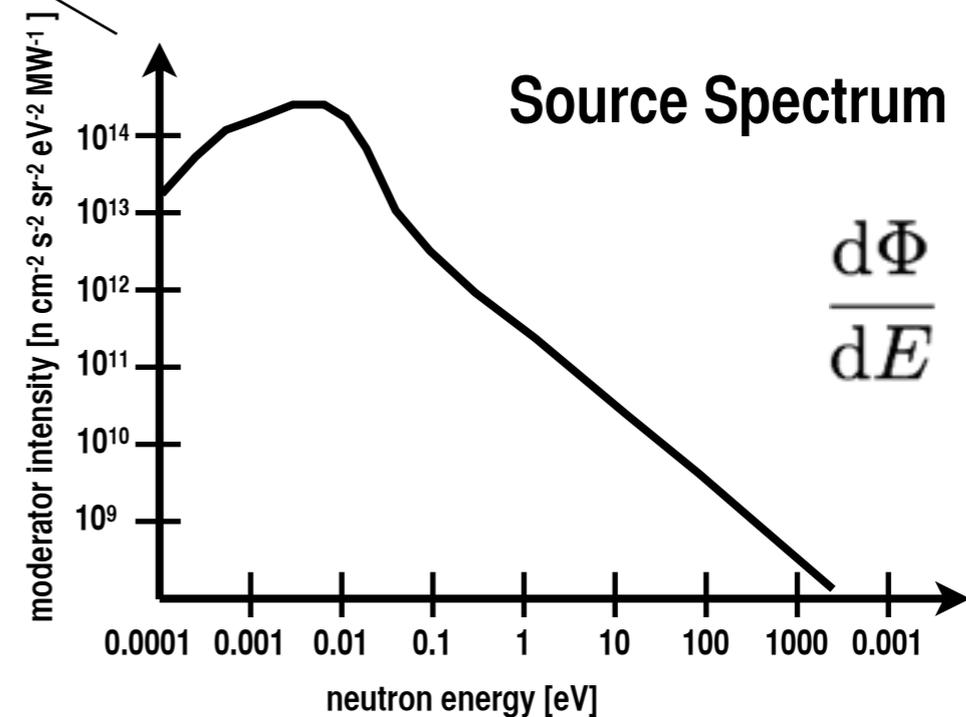
$$\text{FOM} \equiv \langle NT^2 \rangle$$



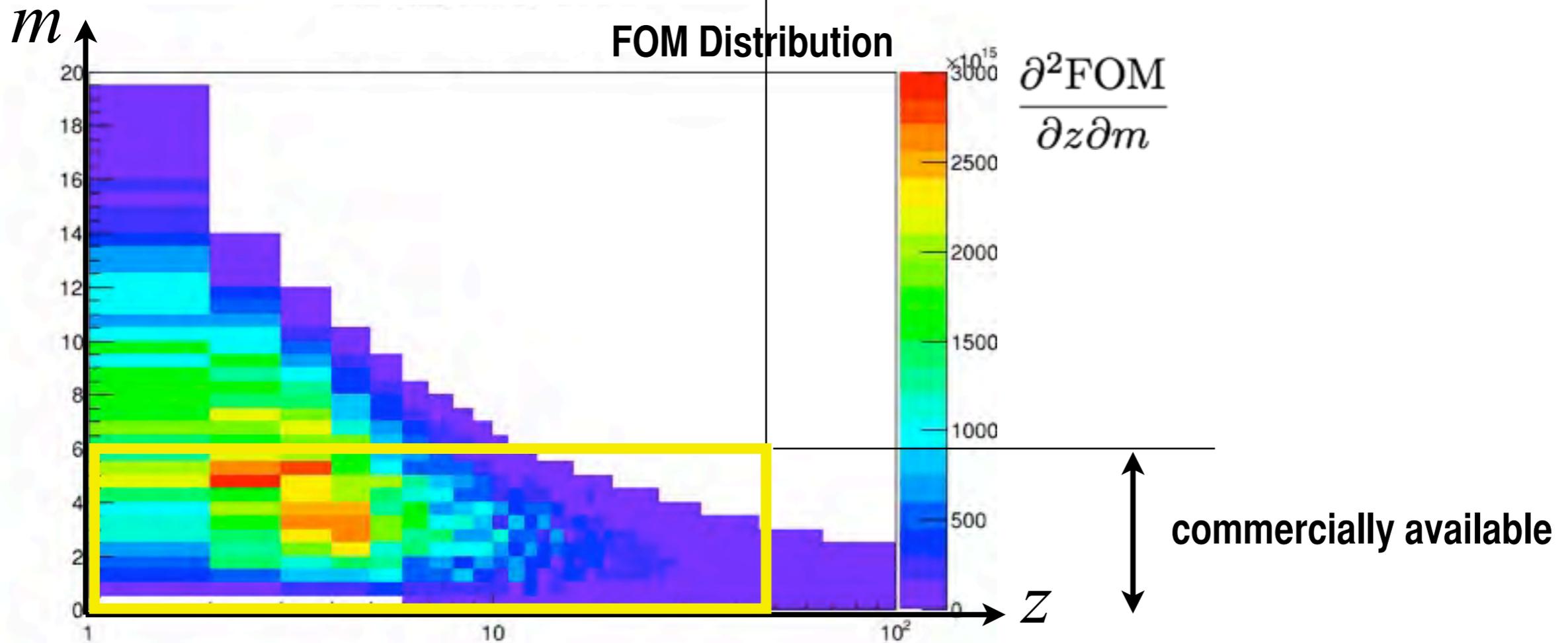
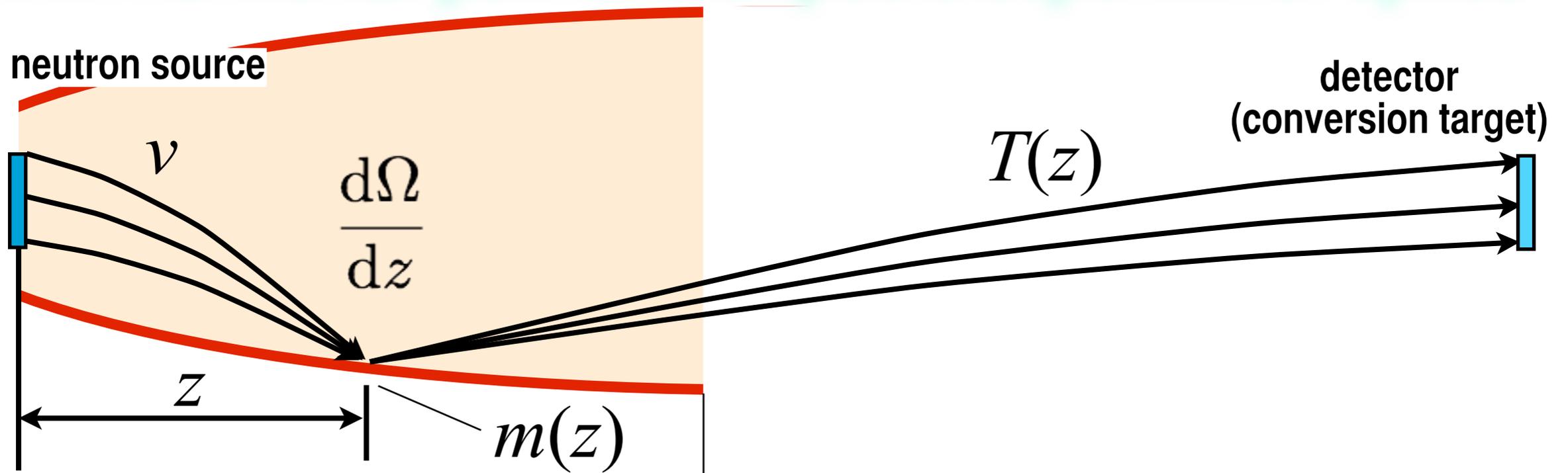
FOM Distribution



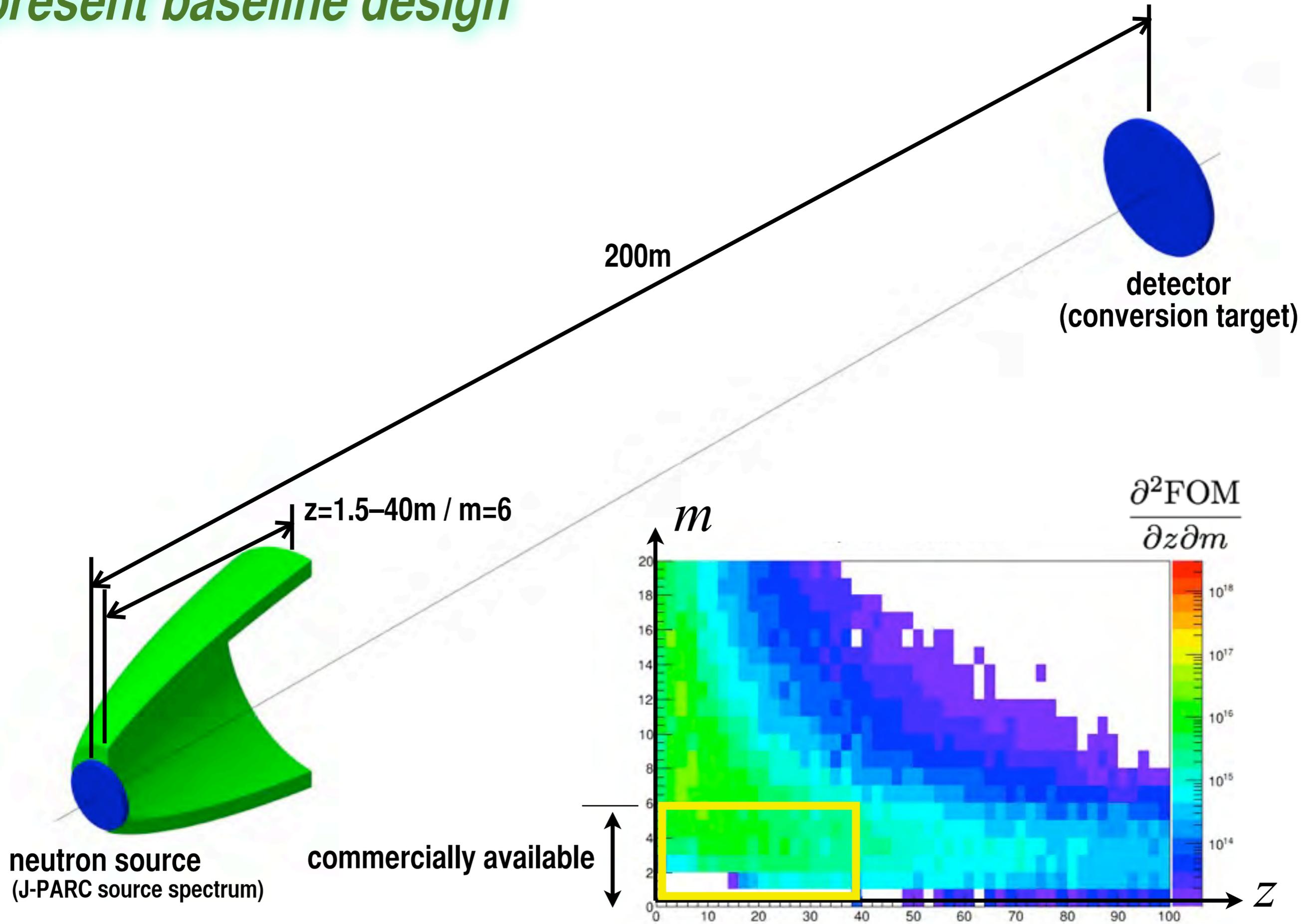
Source Spectrum



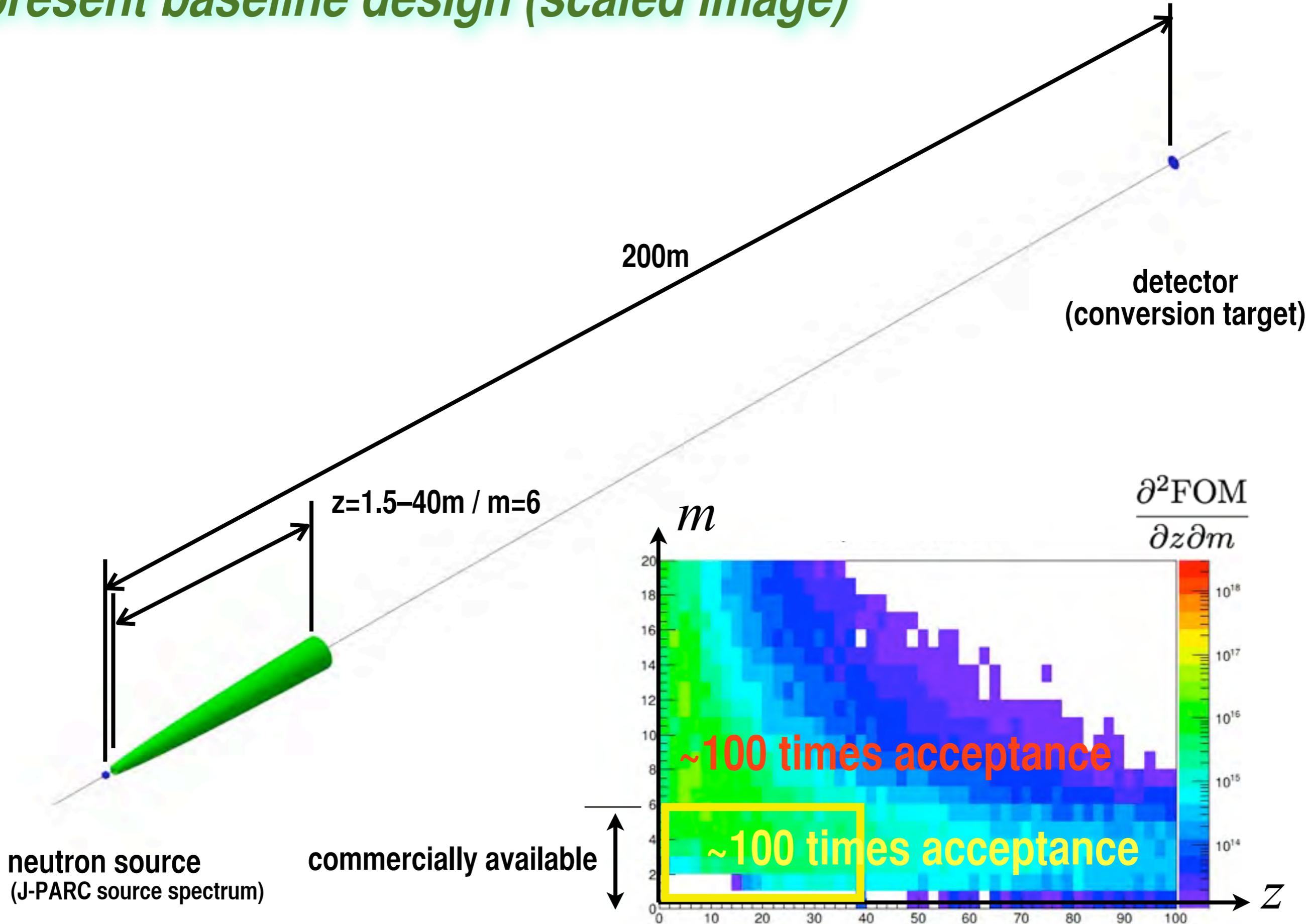
$n\bar{n}$ with horizontal path and ellipsoid supermirror optics



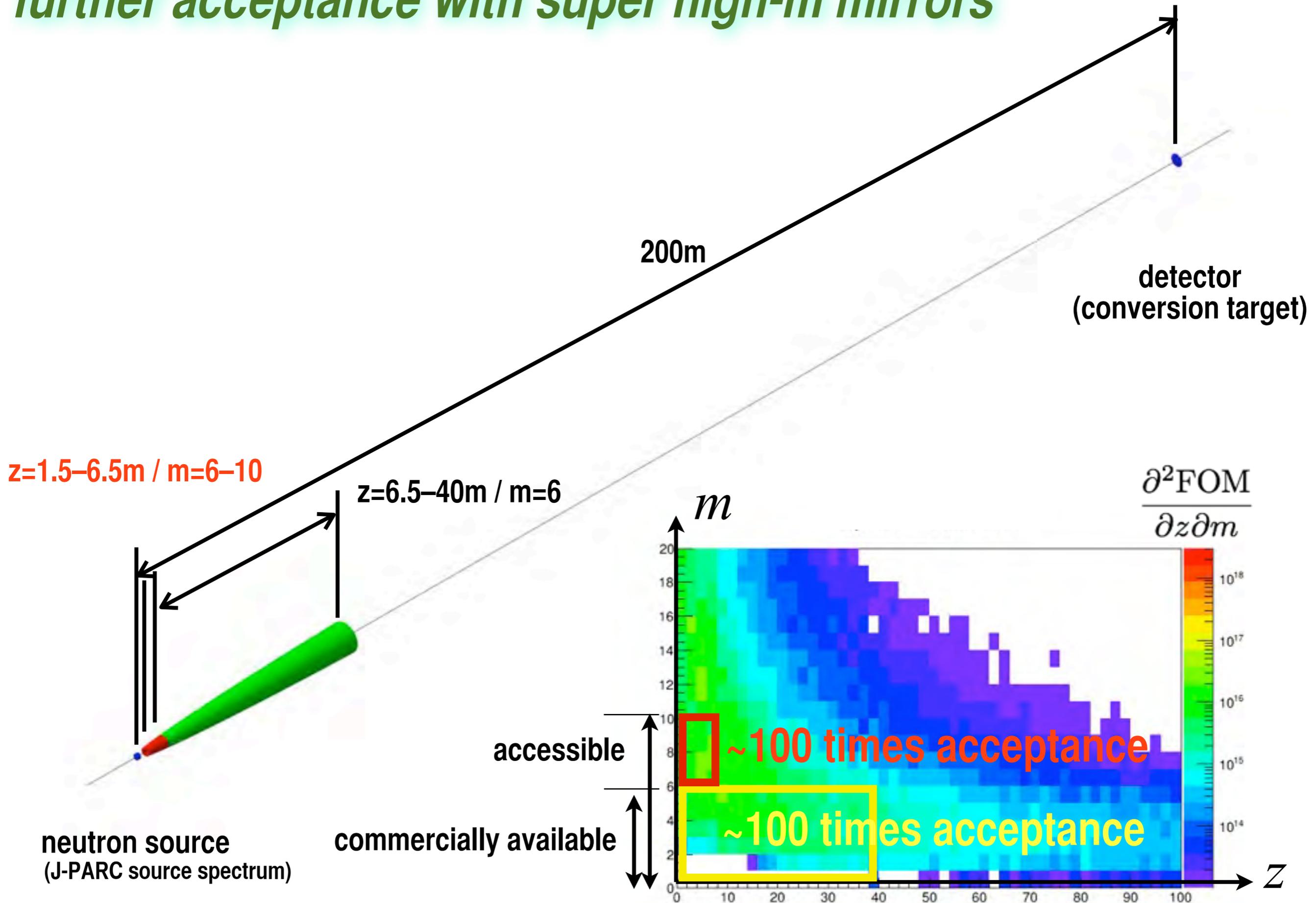
present baseline design



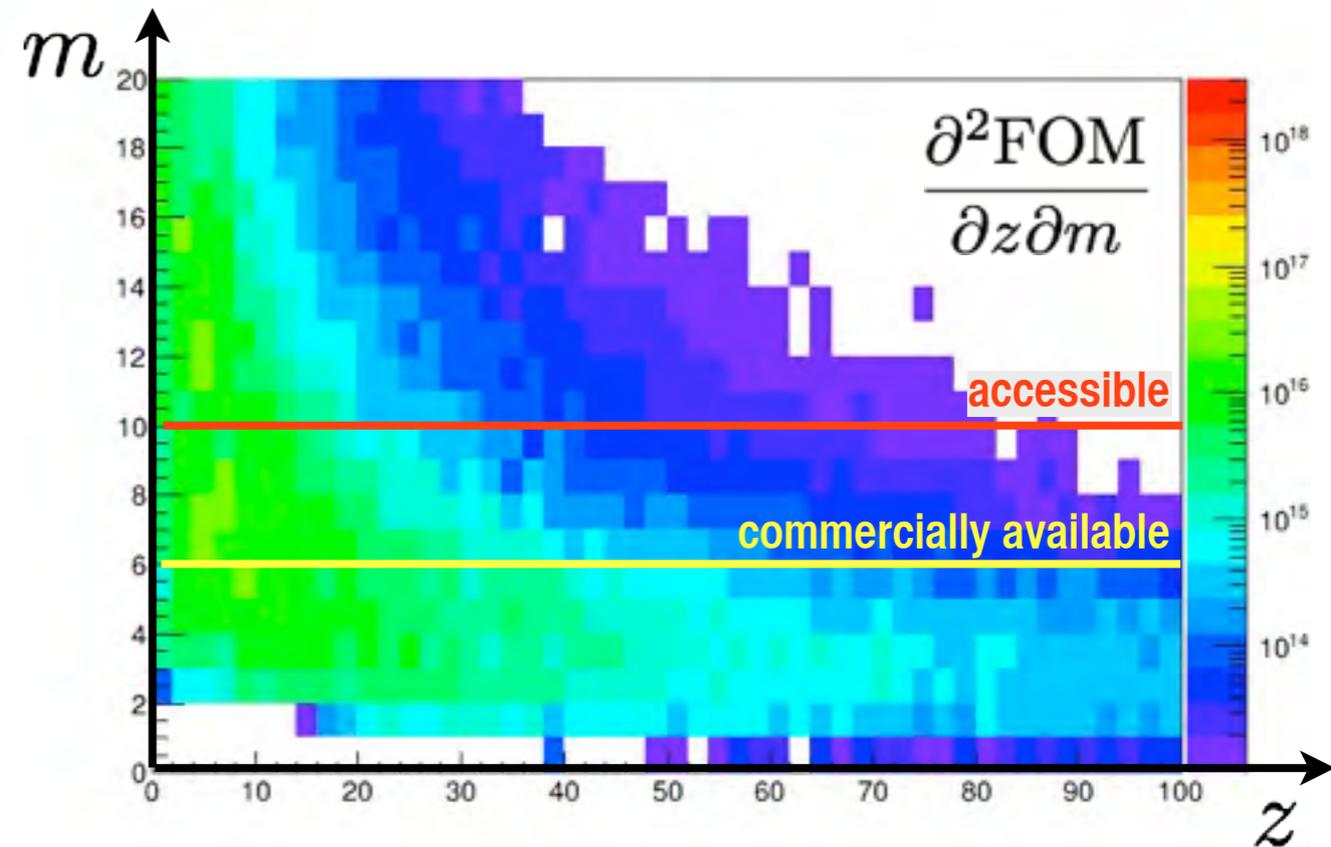
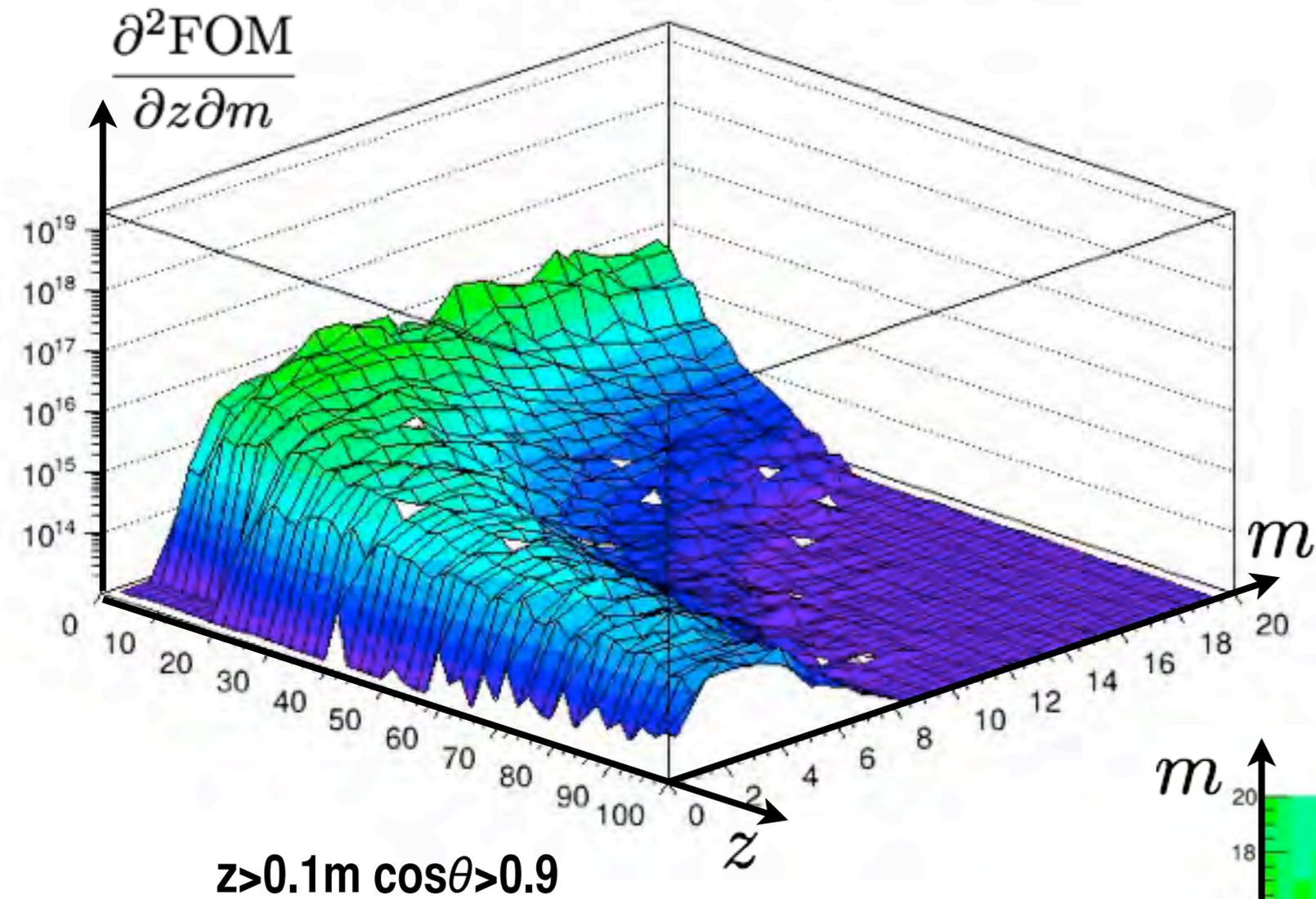
present baseline design (scaled image)



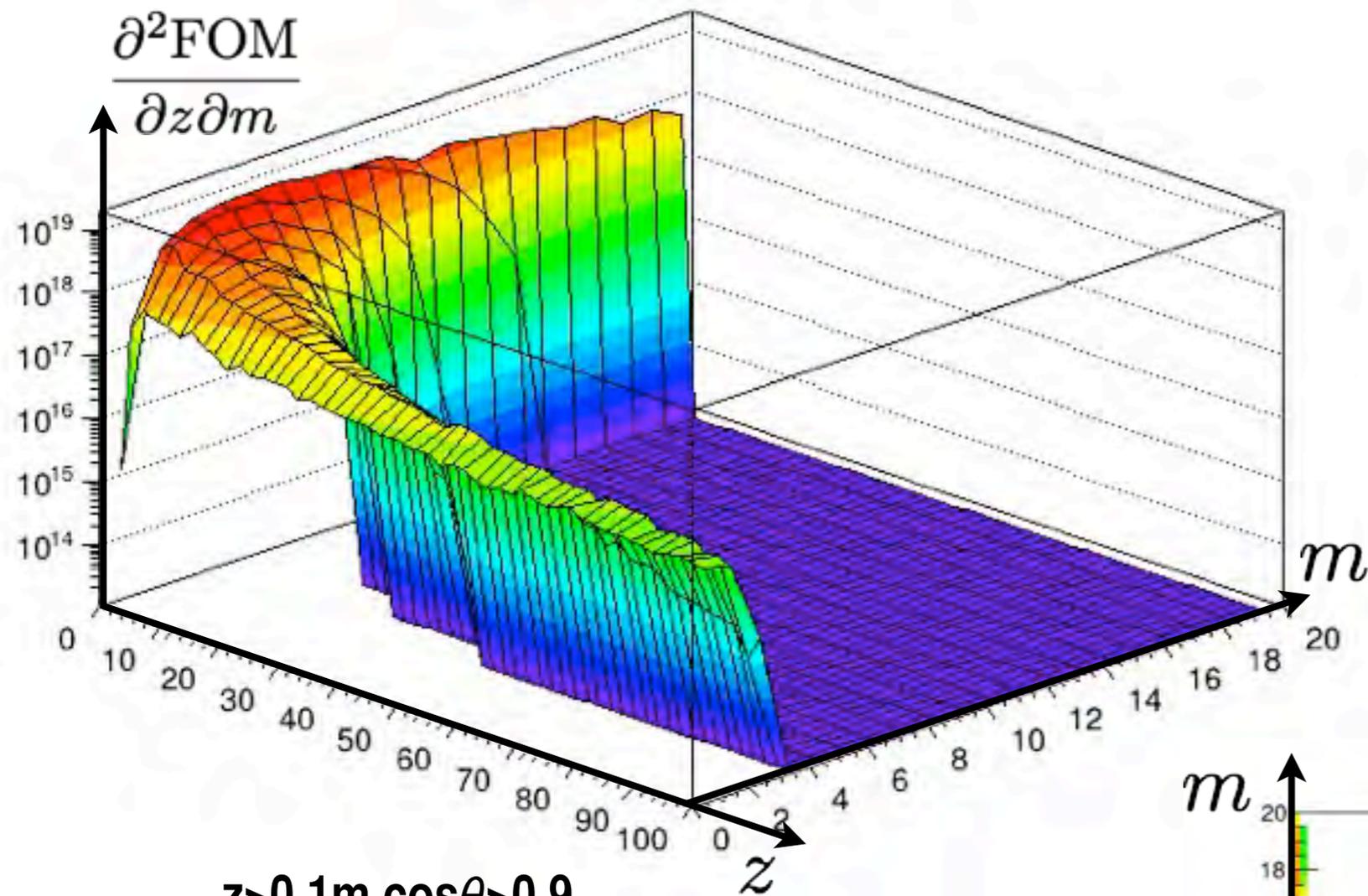
further acceptance with super high- m mirrors



visualization of the acceptance of horizontal flight path



visualization of the acceptance of vertical flight path

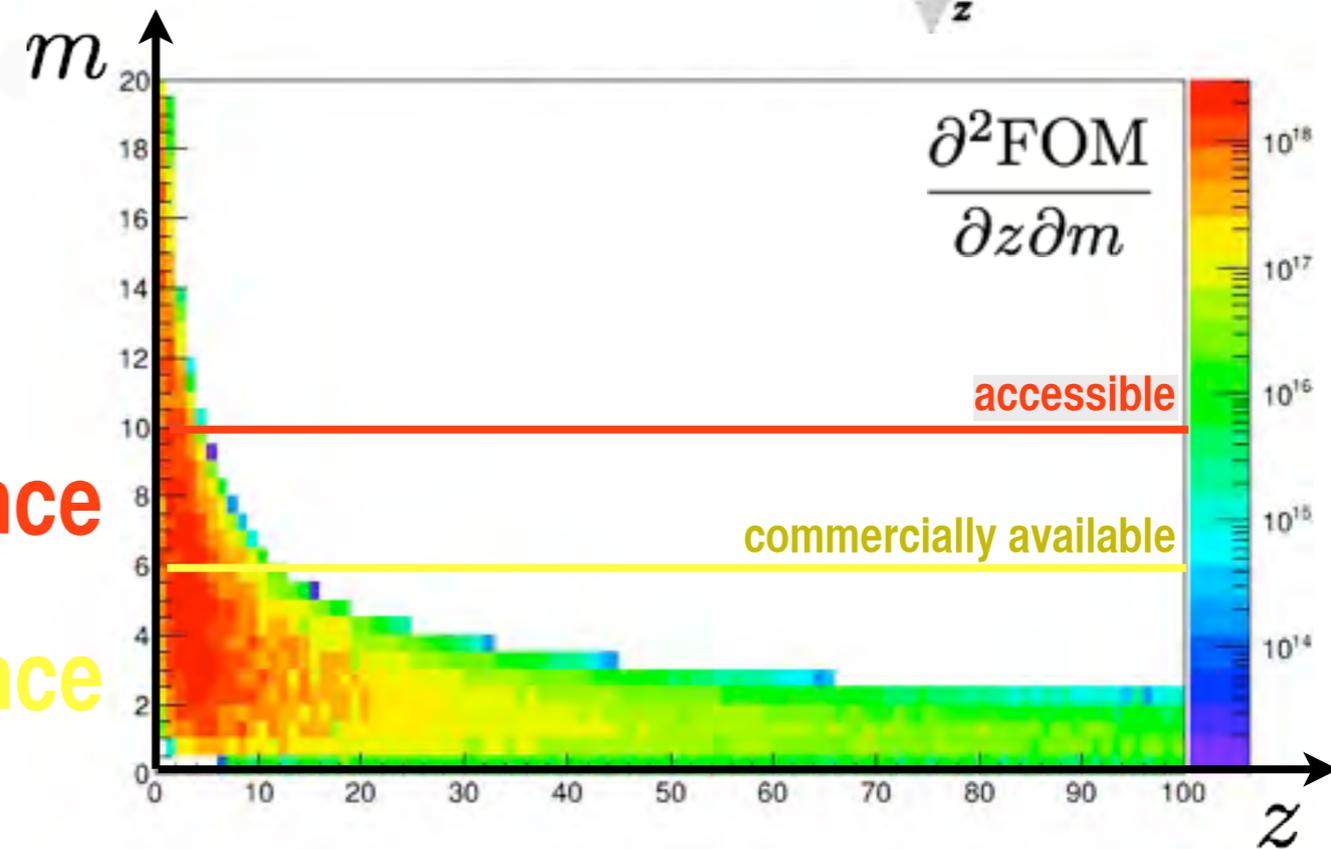


$z > 0.1m \cos\theta > 0.9$



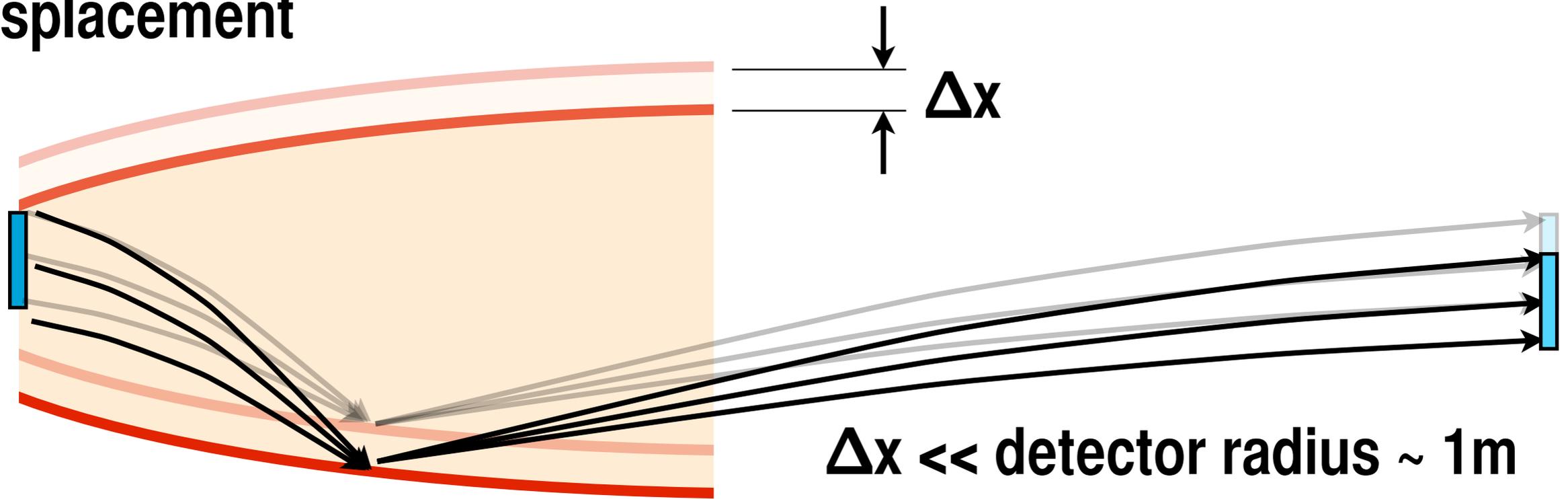
~1000 times acceptance

~1000 times acceptance

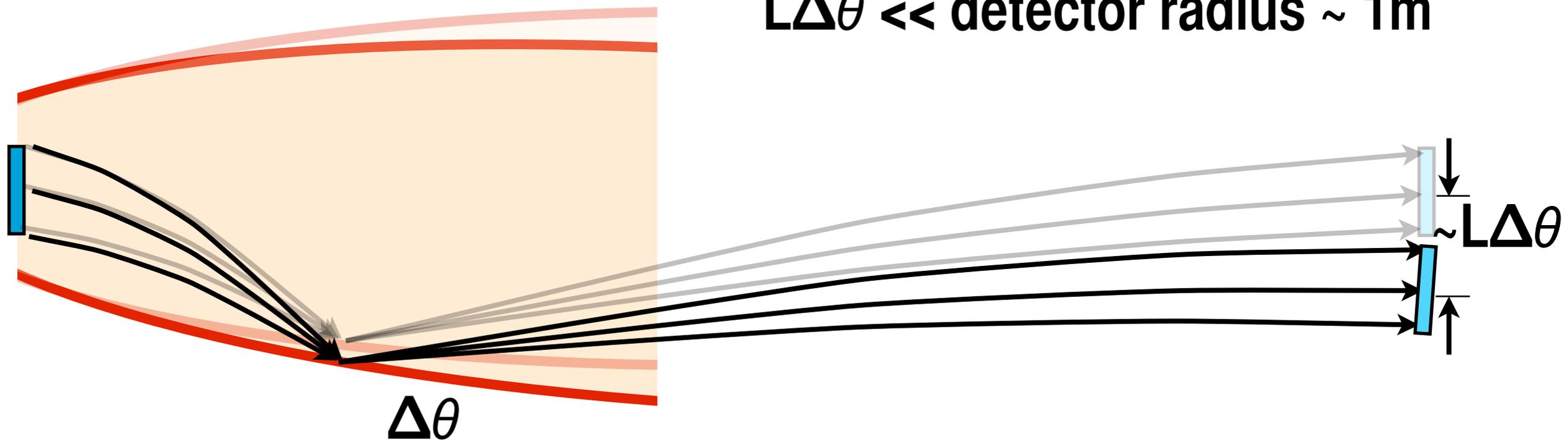


required mirror accuracy

displacement

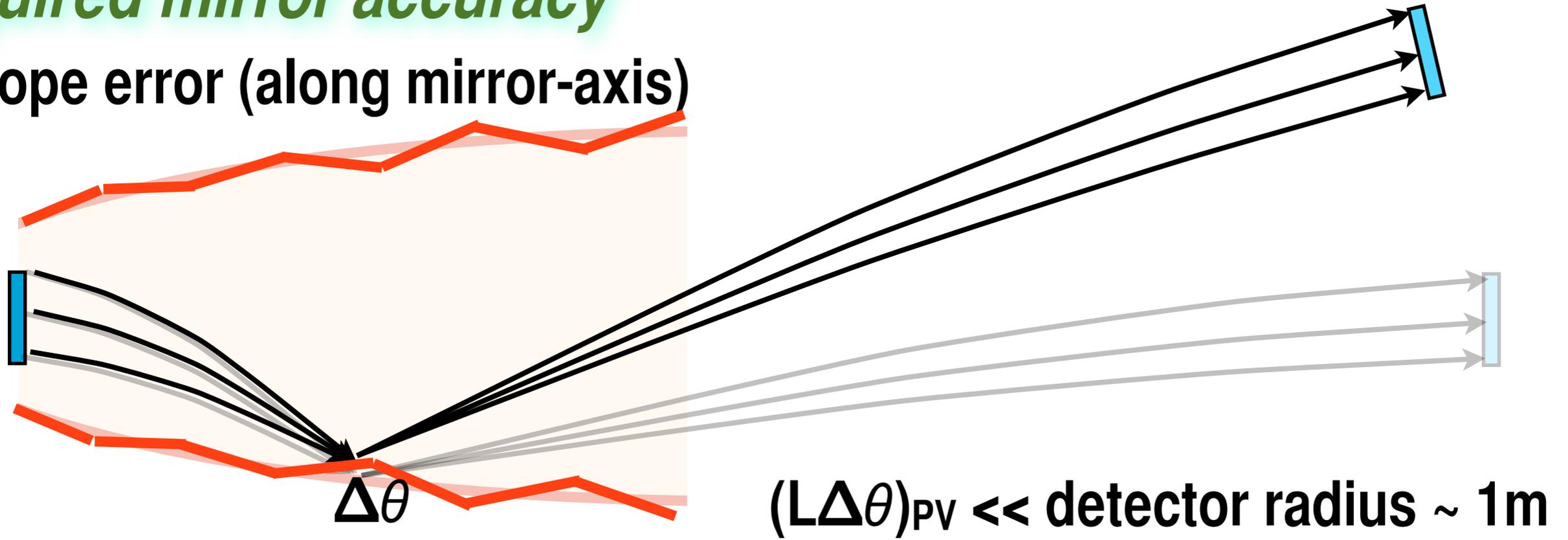


pointing error



required mirror accuracy

slope error (along mirror-axis)

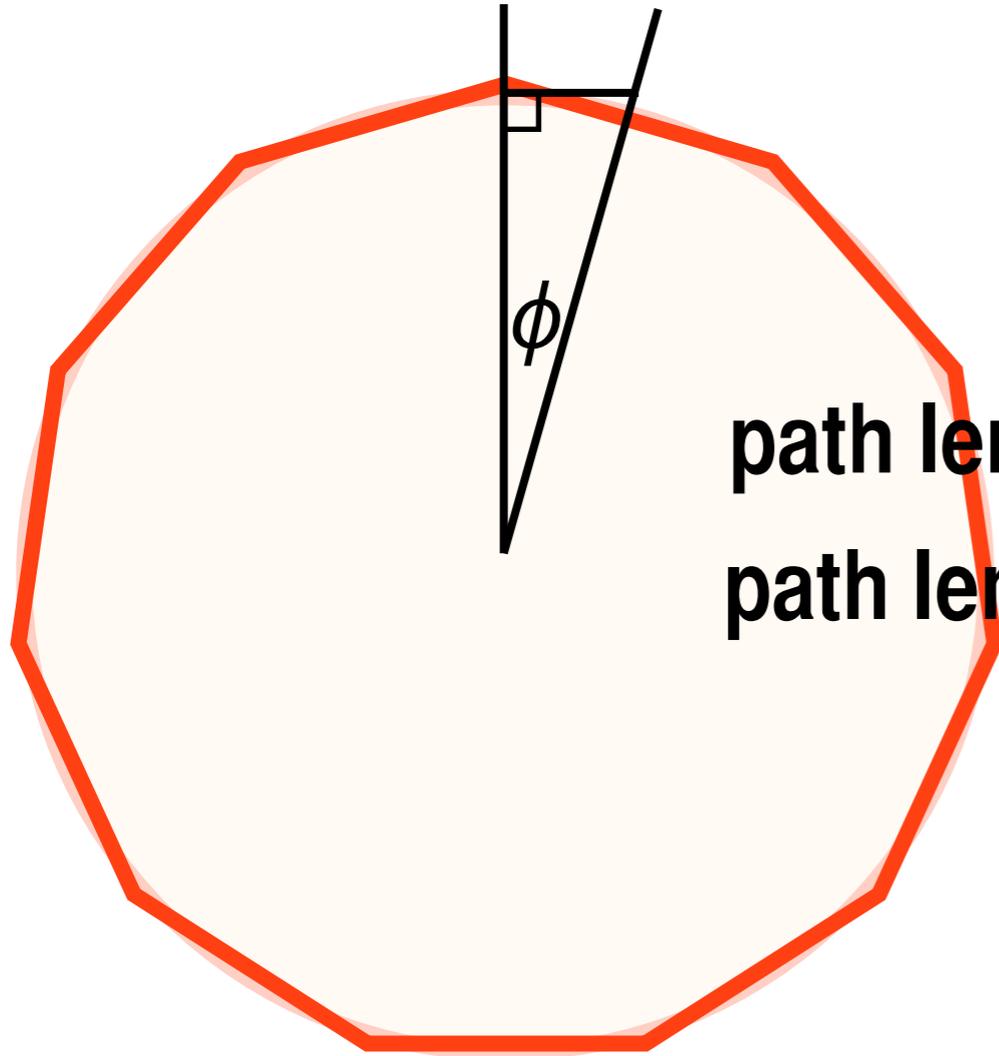


path length = 200m \longrightarrow $(\Delta\theta)_{PV} < 1/200 = 5 \text{ mrad}$

path length = 1000m \longrightarrow $(\Delta\theta)_{PV} < 1/1000 = 1 \text{ mrad}$

required mirror accuracy

limitation to the azimuthal mosaic segmentation



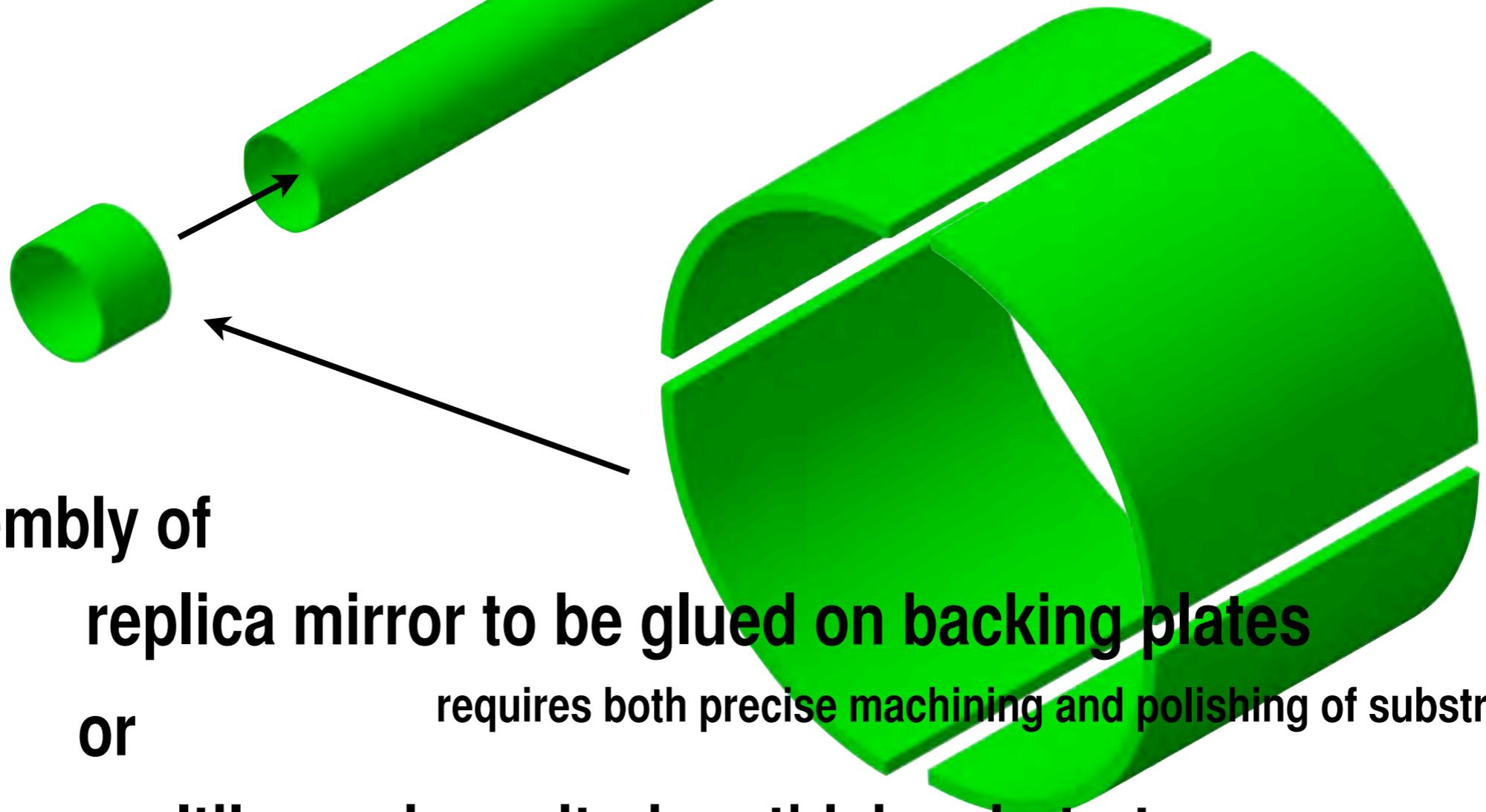
path length = 200m $\longrightarrow \phi < 1/200 = 5 \text{ mrad}$

path length = 1000m $\longrightarrow \phi < 1/1000 = 1 \text{ mrad}$

assembly of segmented mirrors

azimuthal mosaic segmentation is not appropriate

slope error should be controlled below mrad accuracy



assembly of

replica mirror to be glued on backing plates

or

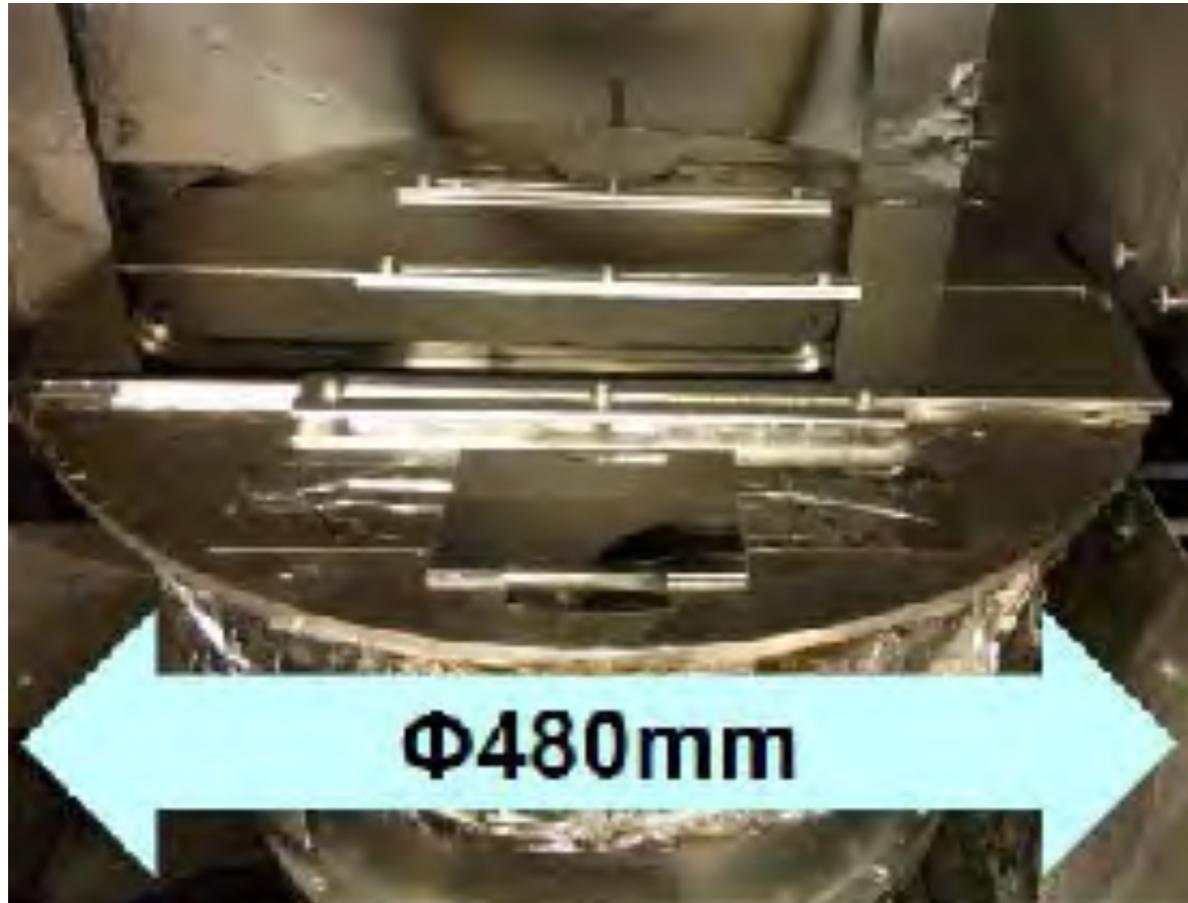
requires both precise machining and polishing of substrates

multilayer deposited on thick substrates

requires relatively less precise machining
requires replica fabrication technique

production of super high-m multilayer mirrors

Ion Beam Sputter @ Kyoto Univ. Research Reactor Inst.



0.1m²/batch

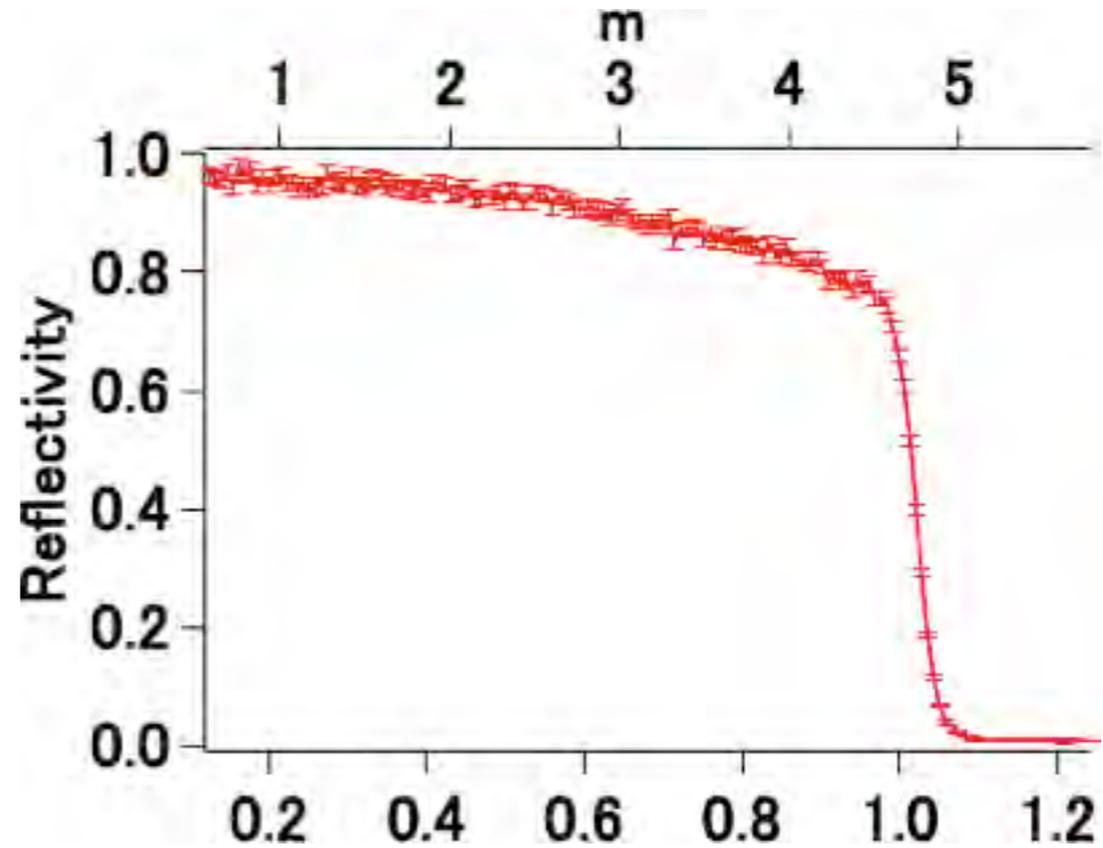
2 batch/day (m=3)

0.2 m²/day/fab.machine

Ion Beam Sputter @ Japan Atomic Energy Agency

(RF Magnetron Sputter for Quicker Mass Production)

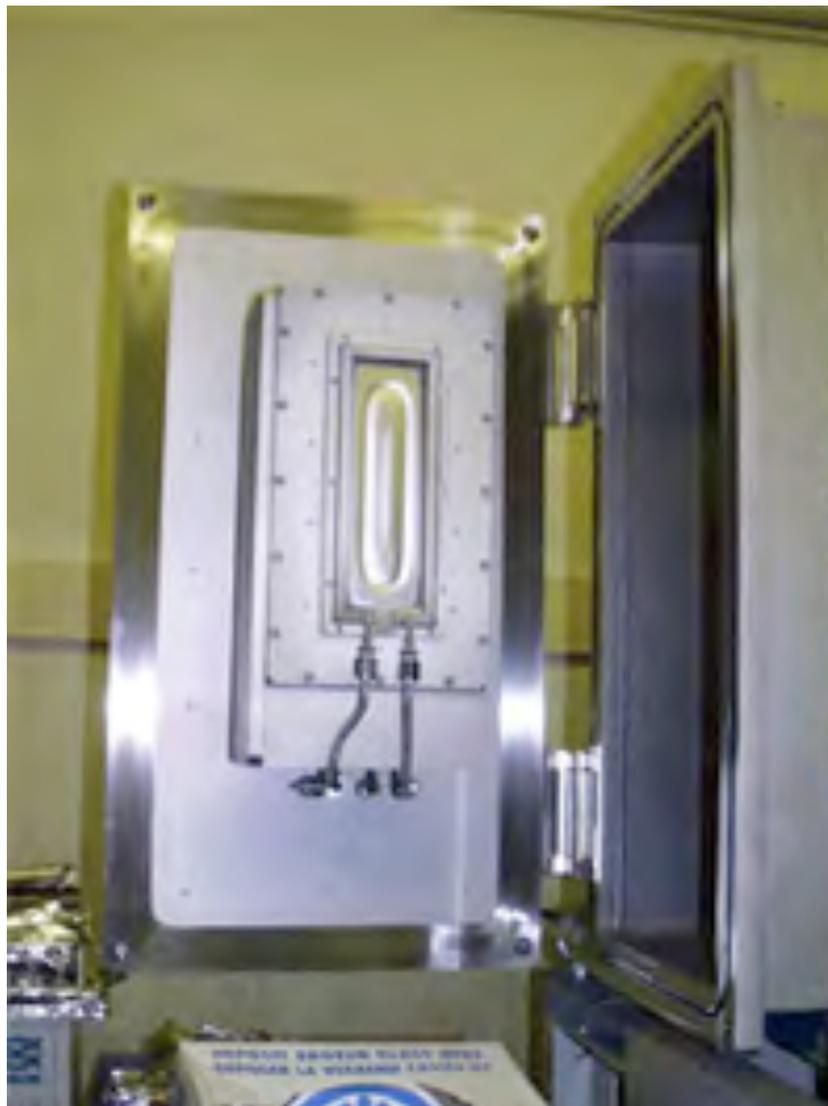
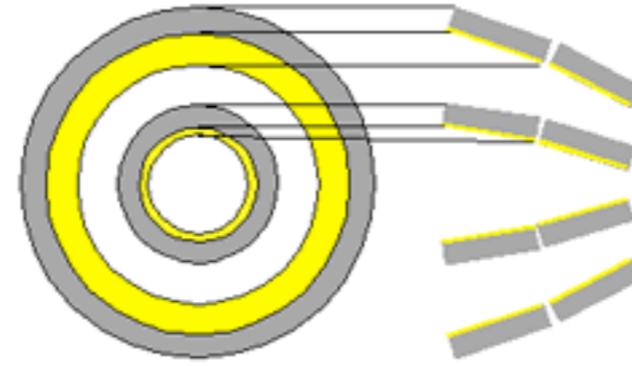
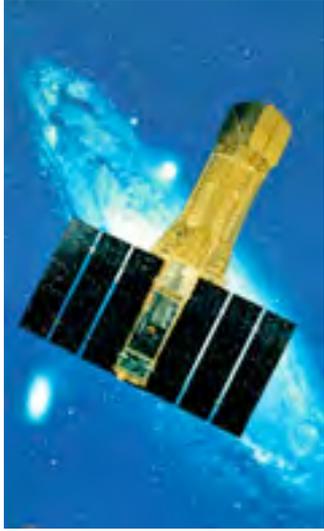
self-sustaining substrateless mirror (replica mirror)



no substrate (radiation hardness expected)

X-ray telescope fabrication skills (replica multilayers)

(Ux-lab. Nagoya Univ.)



X-ray telescope fabrication skills (replica multilayers)

(Ux-lab. Nagoya Univ.)

3 production units and 2 R&D units

DC Magnetron Sputter

Ni-alloy deposition is currently under study.



Summary

optics enhances experimental sensitivity to \bar{n} oscillation

optimization, assembly design, alignment strategy,
mass production of mirrors, ...

adjusting multilayer mirror fabrication skills (in Japan) for mass production

currently man-power limited

Nagoya Univ., Faculty of Science

(proton 2.8MeV)

Hokkaido Univ., Faculty of Engineering

electron 45MeV

for R&D, education

Kyoto Univ., Faculty of Science

proton 3.5MeV

for education

RIKEN, Innovation Center

proton 7MeV

for engineering and industrial applications

KEK, J-PARC

proton 400MeV (3GeV)

for special sources (medical use and UCN)

